

EE 330
Homework Assignment 4
Fall 2018 (Due Friday Feb 8th)

Problem 1 3.1 of Weste and Harris (WH)

Problem 2 3.2 of WH

Problem 3 An aluminum interconnect $250\mu\text{m}$ long and $3\mu\text{m}$ wide has a measured resistance of 25Ω . Determine the thickness of the aluminum interconnect and the sheet resistance. Obtain resistivity from Chapter 6.2 in WH.

Problem 4 If a copper interconnect has the same thickness and the same width as the aluminum interconnect in Problem 3, how long could it be if it also had the same resistance?

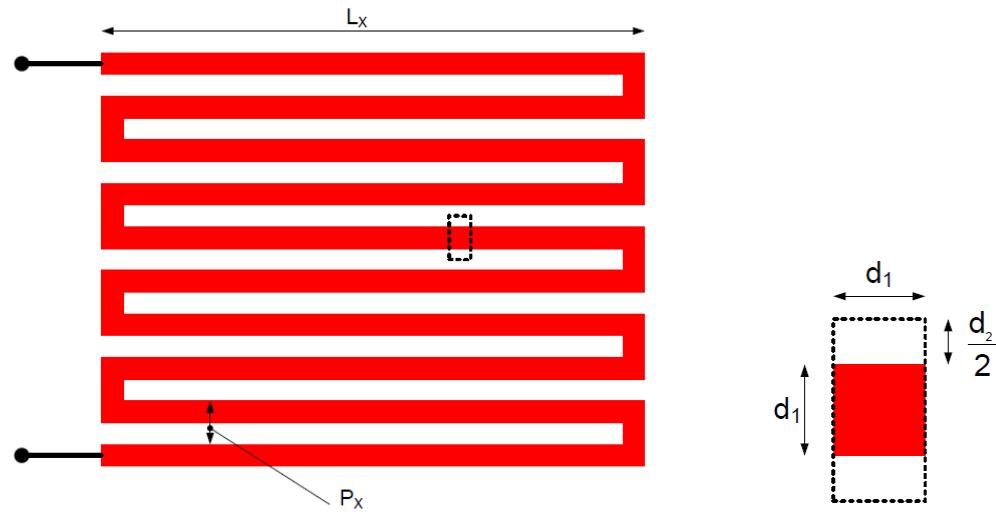
Problem 5 Compare the area required for the layout of a 5K resistor using Poly to that required using p+ diffusion in the TSMC 0.18μ CMOS process. Use a serpentine layout with minimum width and minimum spacing for the resistive elements and be sure that you meet the design rules of the process.

Minimum Dimensions	Width (d_1)	Spacing (d_2)
Poly	2λ	2λ
P+	3λ	3λ

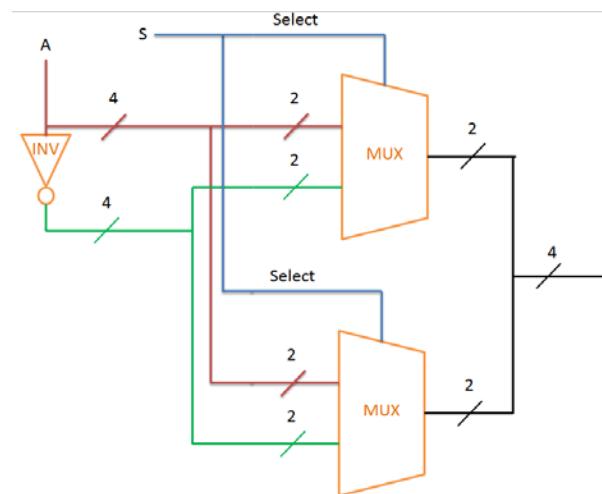
(Continued)

Serpentine layout:

A serpentine (sometimes termed “meander”) layout is shown below. For large valued resistors, the length L_x is generally much larger than the pitch, P_x . The dashed box which includes exactly one square of resistance is expanded below. The dimension d_1 corresponds to the minimum width of the “one-square” resistor and d_2 to the minimum spacing between the serpentine resistor stripes.



Problem 6 Using ModelSim create a 4-bit inverter, then connect it with 2-1 MUXes from last week to choose the original 4-bit input when the select bit is 0 and the inverted 4-bit value when the select bit is 1. Create a test bench for the code and show the following results/waveforms.



MOSIS WAFER ACCEPTANCE TESTS

RUN: T4BK (MM_NON-EPI_THK-MTL)
 TECHNOLOGY: SCN018

VENDOR: TSMC
 FEATURE SIZE: 0.18 microns

INTRODUCTION: This report contains the lot average results obtained by MOSIS from measurements of MOSIS test structures on each wafer of this fabrication lot. SPICE parameters obtained from similar measurements on a selected wafer are also attached.

COMMENTS: DSCN6M018_TSMC

TRANSISTOR PARAMETERS	W/L	N-CHANNEL	P-CHANNEL	UNITS
-----------------------	-----	-----------	-----------	-------

MINIMUM V _{th}	0.27/0.18	0.50	-0.53	volts
-------------------------	-----------	------	-------	-------

SHORT I _{dss}	20.0/0.18	571	-266	uA/um
V _{th}		0.51	-0.53	volts
V _{pt}		4.7	-5.5	volts

WIDE I _{ds0}	20.0/0.18	22.0	-5.6	pA/um
-----------------------	-----------	------	------	-------

LARGE V _{th}	50/50	0.42	-0.41	volts
V _{jbkd}		3.1	-4.1	volts
I _{jlk}		<50.0	<50.0	pA

K' (U _o *C _{ox} /2)	171.8	-36.3	uA/V ²
Low-field Mobility	398.02	84.10	cm ² /V*s

COMMENTS: Poly bias varies with design technology. To account for mask bias use the appropriate value for the parameters XL and XW in your SPICE model card.

Design Technology	XL (um)	XW (um)
-----	-----	-----
SCN6M_DEEP (lambda=0.09)	0.00	-0.01
thick oxide	0.00	-0.01
SCN6M_SUBM (lambda=0.10)	-0.02	0.00
thick oxide	-0.02	0.00

FOX TRANSISTORS	GATE	N+ACTIVE	P+ACTIVE	UNITS
V _{th}	Poly	>6.6	<-6.6	volts

PROCESS PARAMETERS	N+	P+	POLY	N+BLK	PLY+BLK	M1	M2	UNITS
Sheet Resistance	6.6	7.5	7.7	61.0	317.1	0.08	0.08	ohms/sq
Contact Resistance	10.1	10.6		9.3			4.18	ohms
Gate Oxide Thickness	40							angstrom

PROCESS PARAMETERS	M3	POLY_HRI	M4	M5	M6	N_W	UNITS
Sheet Resistance	0.08	991.5	0.08	0.08	0.01	941	ohms/sq
Contact Resistance	8.97		14.09	18.84	21.44		ohms

COMMENTS: BLK is silicide block.

CAPACITANCE PARAMETERS

	N+	P+	POLY	M1	M2	M3	M4	M5	M6	R_W	D_N_W	M5P	N_W	UNITS
Area (substrate)	998	1152	103	39	19	13	9	8	3		129		127	aF/um^2
Area (N+active)			8566	54	21	14	11	10	9					aF/um^2
Area (P+active)			8324											aF/um^2
Area (poly)				64	18	10	7	6	5					aF/um^2
Area (metal1)					44	16	10	7	5					aF/um^2
Area (metal2)						38	15	9	7					aF/um^2
Area (metal3)							40	15	9					aF/um^2
Area (metal4)								37	14					aF/um^2
Area (metal5)									36			1003		aF/um^2
Area (r well)	987													aF/um^2
Area (d well)										574				aF/um^2
Area (no well)	139													aF/um^2
Fringe (substrate)	244	201		18	61	55	43	25						aF/um
Fringe (poly)			69	39	29		24	21	19					aF/um
Fringe (metal1)				61	35			23	21					aF/um
Fringe (metal2)					54	37	27	24						aF/um
Fringe (metal3)						56	34	31						aF/um
Fringe (metal4)							58	40						aF/um
Fringe (metal5)								61						aF/um
Overlap (P+active)			652											aF/um

CIRCUIT PARAMETERS

	K	UNITS
Inverters		
Vinv	1.0	volts
Vinv	1.5	volts
Vol (100 uA)	2.0	volts
Voh (100 uA)	2.0	volts
Vinv	2.0	volts
Gain	2.0	-23.33
Ring Oscillator Freq.		
D1024_THK (31-stg,3.3V)	338.22	MHz
DIV1024 (31-stg,1.8V)	402.84	MHz
Ring Oscillator Power		
D1024_THK (31-stg,3.3V)	0.07	uW/MHz/gate
DIV1024 (31-stg,1.8V)	0.02	uW/MHz/gate

COMMENTS: DEEP_SUBMICRON

SPICE 3f5 Level 8, Star-HSPICE Level 49, UTMOST Level 8

* DATE: Jan 21/05

* LOT: T4BK WAF: 3004

* Temperature_parameters=Default

.MODEL CMOSN NMOS (

+VERSION = 3.1	TNOM = 27	LEVEL = 49
+XJ = 1E-7	NCH = 2.3549E17	TOX = 4E-9
+K1 = 0.5802748	K2 = 3.124029E-3	VTH0 = 0.3662648
+K3B = 3.3886871	W0 = 1E-7	K3 = 1E-3
+DVT0W = 0	DVT1W = 0	NLX = 1.766159E-7
+DVT0 = 1.2312416	DVT1 = 0.3849841	DVT2 = 0.0161351
+U0 = 265.1889031	UA = -1.506402E-9	UB = 2.489393E-18
+UC = 5.621884E-11	VSAT = 1.017932E5	A0 = 2
+AGS = 0.4543117	B0 = 3.433489E-7	B1 = 5E-6
+KETA = -0.0127714	A1 = 1.158074E-3	A2 = 1
+RDSW = 136.5582806	PRWG = 0.5	PRWB = -0.2
+WR = 1	WINT = 0	LINT = 1.702415E-8
+XL = 0	XW = -1E-8	DWG = -4.211574E-9
+DWB = 1.107719E-8	VOFF = -0.0948017	NFACTOR = 2.1860065
+CIT = 0	CDSC = 2.4E-4	CDSCD = 0
+CDSCB = 0	ETA0 = 3.335516E-3	ETAB = 6.028975E-5
+DSUB = 0.0214781	PCLM = 0.6602119	PDIBLC1 = 0.1605325
+PDIBLC2 = 3.287142E-3	PDIBLCB = -0.1	DROUT = 0.7917811
+PSCBE1 = 6.420235E9	PSCBE2 = 4.122516E-9	PVAG = 0.0347169
+DELTA = 0.01	RSH = 6.6	MOBMOD = 1
+PRT = 0	UTE = -1.5	KT1 = -0.11
+KT1L = 0	KT2 = 0.022	UA1 = 4.31E-9
+UB1 = -7.61E-18	UC1 = -5.6E-11	AT = 3.3E4
+WL = 0	WLN = 1	WW = 0
+WWN = 1	WWL = 0	LL = 0
+LLN = 1	LW = 0	LWN = 1
+LWL = 0	CAPMOD = 2	XPART = 0.5
+CGDO = 8.06E-10	CGSO = 8.06E-10	CGBO = 1E-12
+CJ = 9.895609E-4	PB = 0.8	MJ = 0.3736889
+CJSW = 2.393608E-10	PBSW = 0.8	MJSW = 0.1537892
+CJSWG = 3.3E-10	PBSWG = 0.8	MJSWG = 0.1537892
+CF = 0	PVTH0 = -1.73163E-3	PRDSW = -1.4173554
+PK2 = 1.600729E-3	WKETA = 1.601517E-3	LKETA = -3.255127E-3
+PU0 = 5.2024473	PUA = 1.584315E-12	PUB = 7.446142E-25
+PVSAT = 1.686297E3	PETA0 = 1.001594E-4	PKETA = -2.039532E-3

)

```

.MODEL CMOSP PMOS (
+VERSION = 3.1
+XJ      = 1E-7
+K1      = 0.5895473
+K3B     = 13.8642028
+DVT0W   = 0
+DVT0    = 0.7885088
+U0      = 103.0478426
+UC      = -1E-10
+AGS     = 0.3295499
+KETA    = 0.0296157
+RDSW    = 306.5789827
+WR      = 1
+XL      = 0
+DWB     = -9.34648E-11
+CIT     = 0
+CDSCB   = 0
+DSUB    = 1.094521E-3
+PDIBLC2 = -3.255915E-6
+PSCBE1  = 4.881933E10
+DELTA   = 0.01
+PRT     = 0
+KT1L    = 0
+UB1     = -7.61E-18
+WL      = 0
+WWN     = 1
+LLN     = 1
+LWL     = 0
+CGDO    = 6.52E-10
+CJ      = 1.157423E-3
+CJSW    = 1.902456E-10
+CJSWG   = 4.22E-10
+CF      = 0
+PK2     = 2.190431E-3
+PU0     = -0.9769623
+PVSAT   = -50
)
TNOM    = 27
NCH     = 4.1589E17
K2      = 0.0235946
W0      = 1E-6
DVT1W   = 0
DVT1    = 0.2564577
UA      = 1.049312E-9
VSAT    = 1.645114E5
B0      = 5.207699E-7
A1      = 0.4449009
PRWG    = 0.5
WINT    = 0
XW      = -1E-8
VOFF    = -0.0867009
CDSC    = 2.4E-4
ETA0    = 1.018318E-3
PCLM    = 1.3281073
PDIBLCB = -1E-3
PSCBE2  = 5E-10
RSH     = 7.5
UTE     = -1.5
KT2     = 0.022
UC1     = -5.6E-11
WLN     = 1
WWL     = 0
LW      = 0
CAPMOD  = 2
CGSO    = 6.52E-10
PB      = 0.8444261
PBSW    = 0.8
PBSWG   = 0.8
PVTH0   = 1.4398E-3
WKETA   = 0.0442978
PUA     = -4.34529E-11
PETA0   = 1.002762E-4
LEVEL   = 49
TOX     = 4E-9
VTH0   = -0.3708038
K3      = 0
NLX     = 1.517201E-7
DVT2W   = 0
DVT2    = 0.1
UB      = 2.545758E-21
A0      = 1.627879
B1      = 1.370868E-6
A2      = 0.3
PRWB    = 0.5
LINT    = 2.761033E-8
DWG     = -2.433889E-8
NFACTOR = 2
CDSCD   = 0
ETAB    = -3.206319E-4
PDIBLC1 = 2.394169E-3
DROUT   = 0
PVAG    = 2.0932623
MOBMOD  = 1
KT1     = -0.11
UA1     = 4.31E-9
AT      = 3.3E4
WW      = 0
LL      = 0
LWN     = 1
XPART   = 0.5
CGBO    = 1E-12
MJ      = 0.4063933
MJSW    = 0.3550788
MJSWG   = 0.3550788
PRDSW   = 0.5073407
LKETA   = -2.936093E-3
PUB     = 1E-21
PKETA   = -6.740436E-3
)

```

TRANSISTOR PARAMETERS W/L N-CHANNEL P-CHANNEL UNITS

MINIMUM Vth	3.0/0.6					
		0.78	-0.93	volts		
SHORT Idss	20.0/0.6	439	-238	uA/um		
Vth		0.69	-0.90	volts		
Vpt		10.0	-10.0	volts		
WIDE Ids0	20.0/0.6	< 2.5	< 2.5	pA/um		
LARGE Vth	50/50	0.70	-0.95	volts		
Vjbkd		11.4	-11.7	volts		
Ijlk		<50.0	<50.0	pA		
Gamma		0.50	0.58	V^0.5		
K' (Uo*Cox/2)		56.9	-18.4	uA/V^2		
Low-field Mobility		474.57	153.46	cm^2/V*s		

COMMENTS: XL_AMI_C5F

FOX TRANSISTORS	GATE	N+ACTIVE	P+ACTIVE	UNITS
Vth	Poly	>15.0	<-15.0	volts

PROCESS PARAMETERS	N+ACTV	P+ACTV	POLY	PLY2_HR	POLY2	MTL1	MTL2	UNITS
Sheet Resistance	82.7	103.2	21.7	984	39.7	0.09	0.09	ohms/sq
Contact Resistance	56.2	118.4	14.6		24.0		0.78	ohms
Gate Oxide Thickness	144							angstrom

PROCESS PARAMETERS	MTL3	N\PLY	N_WELL	UNITS
Sheet Resistance	0.05	824	815	ohms/sq
Contact Resistance	0.78			ohms

COMMENTS: N\POLY is N-well under polysilicon.

CAPACITANCE PARAMETERS	N+ACTV	P+ACTV	POLY	POLY2	M1	M2	M3	N_WELL	UNITS
Area (substrate)	429	721	82		32	17	10	40	aF/um^2
Area (N+active)			2401		36	16	12		aF/um^2
Area (P+active)			2308						aF/um^2
Area (poly)				864	61	17	9		aF/um^2
Area (poly2)					53				aF/um^2
Area (metall1)						34	13		aF/um^2
Area (metal2)							32		aF/um^2
Fringe (substrate)	311	256			74	58	39		aF/um
Fringe (poly)					53	40	28		aF/um
Fringe (metall1)						55	32		aF/um
Fringe (metal2)							48		aF/um
Overlap (N+active)			206						aF/um
Overlap (P+active)			278						aF/um